

ABSTRACT OF THE DISCLOSURE

A method of controlling the sheet resistance of metal silicide regions by controlling the silicide strip time is provided. In one illustrative embodiment, the method comprises forming a layer comprised of a refractory metal, determining a thickness of the layer of refractory metal, and converting a portion of the layer of refractory metal to a metal silicide. 5 The method further comprises determining a duration of an etching process to be used to remove unreacted portions of the refractory metal layer based upon the determined thickness of the refractory metal layer, and performing the etching process for the determined duration.